

Notice of References Cited	Application/Control No. 10/590,079	Applicant(s)/Patent Under Reexamination GOTO ET AL.	
	Examiner BRYAN D. RIPA	Art Unit 1795	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,471,745	10-2002	Foley et al.	95/54
*	B	US-7,097,875	08-2006	Clyde et al.	427/115
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Smith et al., "Evaluation of Precursors for Chemical Vapor Deposition of Ruthenium" Thin Solid Films 376, pages 73-81 (2000)
	V	Goto et al., "Electrochemical Properties of Iridium-Carbon Nano Composite Films Prepared by MOCVD" Scripta Materialia 44, pages 1187-1190 (2001)
	W	Kimura et al., "Preparation of RuO2-YSZ Nano-Composite Films by MOCVD" Surface and Coatings Technology 167, pages 240-244 (2003)
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.